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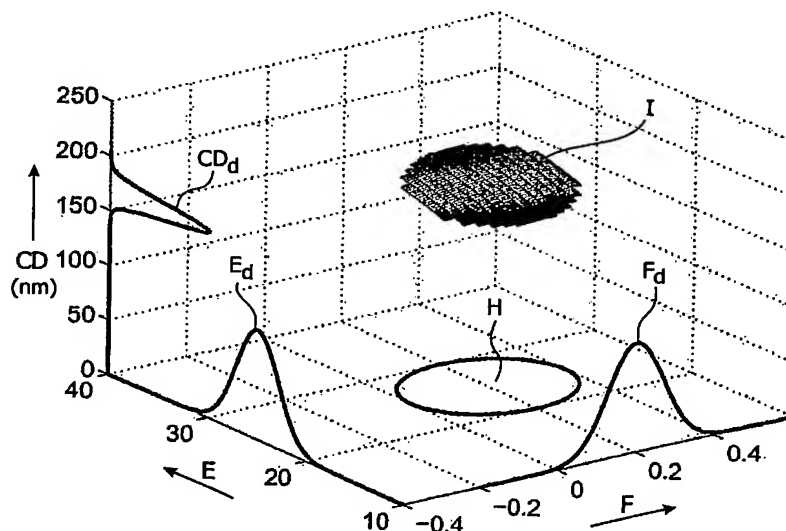
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(54) Title: A METHOD OF DETERMINING BEST PROCESS SETTING FOR OPTIMUM PROCESS WINDOW OPTIMIZING PROCESS PERFORMANCE DETERMINING OPTIMUM PROCESS WINDOW FOR A LITHOGRAPHIC PROCESS



(57) Abstract: For determining best process variables (E, F, W) setting that provide optimum process window for a lithographic process for printing features having critical dimensions (CD) use is made of an overall performance characterizing parameter (C_{pk}) and of an analytical model, which describes CD data as a function of process parameters, like exposure dose (E) and focus (F). This allows calculating of the average value (μCD) and the variance (σCD) of the statistical CD distribution (CDD) and to determine the highest C_{pk} value and the associated values of process parameters, which values provide the optimum process window.

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